

REMARKS

Claims 1, 2 and 4-6 are pending and under consideration in the above-identified application, and Claim 3 was previously cancelled.

In the Office Action, Claims 1, 2 and 4-6 were rejected.

In this Amendment, Claims 1, 2, 4 and 5 are amended, and Claim 6 is cancelled. No new matter has been introduced as a result of this Amendment.

Accordingly, Claims 1, 2, 4 and 5 are at issue.

I. 35 U.S.C. § 103 Obviousness Rejection of Claims 1-2 and 4-6

Claims 1-2 and 4-6 were rejected under 35 U.S.C. § 103(a) as being unpatentable over *Tsuda et al.* (“*Tsuda*”) (U.S. Patent No. 5,936,688) in view of *Nakamura et al.* (“*Nakamura*”) (U.S. Patent No. 5,847,789), and in further view of *Itoh et al.* (“*Itoh*”) (U.S. Patent No. 6,094,252). Although, Applicants respectfully traverse this rejection, to further prosecution, Claim 1 has been amended to clarify the invention and remove any ambiguities that may have been at the basis of this rejection.

Claim 1 has been amended by incorporating the substantive limitations of Claim 6.

In the relevant part, Claim 1 recites “said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight lines providing a gap between thereby formed polygonal pillar-shaped bodies, and said gap having a size equal to about a minimum resolution of said photolithography.” This is clearly unlike *Tsuda*, *Nakamura*, and *Itoh* taken singly or in combination with each other.

Referring to Applicants’ Figures 2 and 3 as an illustrative example, Applicants’ claimed invention comprises a method of manufacturing a diffusing reflector. FIG. 2 illustrates pillar-shaped bodies isolated from each other by polygonal patterning a resin film with photolithography. FIG. 3 illustrates circles in diameter of 11 μ m drawn to be in contact with each other. Next, boundaries of the circles in contact condition are connected continuously with straight lines and are then isolated from each other. The width of the isolating boundary, namely the size of gap between neighboring polygonal pillar-shaped bodies, is set to about 1 μ m which is almost equal to the minimum resolution of the photolithography process.

This Examiner states that in the rejection of Claim 6 that *Tsuda* discloses the resin film (34a) is patterned by the divided patterning means so that the size of the gap between the polygonal pillar-shaped bodies (32c) isolated from each other is almost equal to the minimum resolution of photolithography and points to Column 13, lines 33 – 40 for support.

However, *Tsuda* states in Column 13 that (emphasis added):

“Although the total area of the protrusions 112b is set at a very high proportion of about 80% with respect to the total area of the substrate, the amount of light which is reflected by the regular reflection becomes extremely large. *This results from the interval between the adjacent protrusions 112b to be formed through a single photolithography process being as small as 0.5 μ m. Such a small interval allows adjacent protrusions 112b to be joined with one another when melted, thereby consequently increasing the total area of the flat region.* More specifically, a number of adjacent protrusions 112b form a massive portion. Only the periphery portion of the massive portion forms a curvature by being deformed when heated. Therefore, the other part of the massive portion consequently forms a flat region.”

That is, although in *Tsuda* adjacent protrusions (pillar-shaped bodies) 112b are initially separated by the photolithography process. This separation between the pillar-shaped bodies 112b is as small as 0.5 μ m so that these pillar-shaped bodies are joined with one another when melted, thereby increasing the total area of the flat region. Thus, in *Tsuda* the melted-together pillar-shaped bodies 112b no longer have open flat spaces therebetween them to be covered by a second resin to form one concave gap between two adjacent isolated pillar-shaped bodies 112b. Moreover, FIGs 6G – 6J, 9H – 9I20H – 20L, 21G – 21J of *Tsuda* do not illustrate a continuous polygonal pattern formed by the separating gap, as required by Claim 1.

As such, *Tsuda* fails to teach or suggest a first resin film is patterned by straight connected lines that form a continuous polygonal pattern, straight lines providing a gap between thereby formed polygonal pillar-shaped bodies, and the gap having a size equal to about a minimum resolution of the photolithography. Further, both *Nakamura* and *Itoh* also fail to teach or suggest this distinguishable limitation of Claim 1.

Thus, Claim 1 is patentable over *Tsuda*, *Nakamura*, and *Itoh* taken singly or in combination with each other, as are dependent Claims 2, 4 and 5, for at least the same reasons.

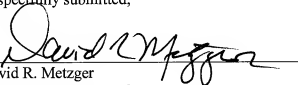
II. Conclusion

In view of the above amendments and remarks, Applicant submits that Claims 1, 2, 4 and 5 are clearly allowable over the cited prior art, and respectfully requests early and favorable notification to that effect.

Respectfully submitted,

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